

IN THE CLAIMS:

Please amend claims 1-20 as follows:

1. (Currently Amended) ~~Method—A method for producing a superconducting inductive component having at least two plots, this—said component comprising at least one line segment incorporating at least one plot of the component, this said line segment constituting a conducting or superconducting layer within a stack (E) of alternately superconducting (C1) and insulating (C2) films.~~

2. (Currently Amended) ~~Method—The method according to claim 1, characterized in that wherein each film constituting the stack (E) is perfectly crystallized.~~

3. (Currently Amended) ~~Method—The method according to one of claims 1 or 2~~claim 1~~, characterized in that it comprises further including a prior step of depositing an insulating film (C2) on a substrate (S).~~

4. (Currently Amended) ~~Method—The method according to one of claims 1 or 2~~claim 1~~, characterized in that it comprises further including a prior step of depositing a superconducting film (C1) on a substrate (S).~~

5. (Currently Amended) Method The method according to one of claims 1 or 2claim 1, characterized in that it comprisesfurther including a prior step of depositing a superconducting film (L1) on a substrate (S) followed by the depositing of the stack (E).

6. (Currently Amended) Method The method according to one of claims 3 or 4claim 3, characterized in that it comprises moreoverfurther including the following steps:

- a deposit of the stack (E) of alternately superconducting (C1) and insulating (C2) films,
- an etching of the stack (E) carried out in such a way that the latter only remains at the locations where an inductive component is to be implanted.

7. (Currently Amended) Method The method according to claim 5, characterized in that it comprises moreover further including the following steps:

- an etching of the stack (E) carried out in such a way that the latter only remains at the locations where an inductive component is to be implanted.
- an etching of the superconducting film (L1).

8. (Currently Amended) ~~Method~~ The method according to claim 5,
characterized in that it ~~comprises moreover further~~ including the following steps:
- a simultaneous etching of the stack (E) and of the superconducting film (L1)
- an etching of the stack (E) carried out in such a way that the latter only
remains at the locations where an inductive component is to be implanted.

9. (Currently Amended) ~~Method~~ The method according to one of the
preceding claims, characterized in that claim 1, wherein at least one of the superconducting
films (C1) is produced from $\text{YB}_{a2}\text{Cu}_3\text{O}_{7-\delta}$ compounds.

10. (Currently Amended) ~~Method~~ The method according to one of the
preceding claims, characterized in that claim 1, wherein at least one of the insulating films
(C2) is made from LaAlO_3 compounds.

11. (Currently Amended) ~~System~~ A system for producing a
superconducting inductive component having at least two plots, ~~this~~ said component
comprising at least one line segment incorporating at least one plot of the component, ~~this~~
said line segment constituting a conducting or superconducting layer within a stack (E) of
alternately superconducting (C1) and insulating (C2) films, implementing the method
according to ~~one of the preceding claims~~ claim 1.

12. (Currently Amended) System The system according to claim 11,
characterized in that it comprises further including:

- means for depositing a stack (E) of alternately superconducting and insulating films, and
- means for etching all of the deposited films, these said means being arranged in such a way that said deposited films remain only at the locations where an inductive component is to be implanted.

13. (Currently Amended) System The system according to claim 11,
characterized in that it comprises further including:

- means for depositing a superconducting film (L1) on a substrate (S),
- means for depositing on the superconducting film (L1) a stack (E) of alternately superconducting and insulating films, and
- means for etching all of the deposited films, these means being arranged in such a way that the film (L1) remains only at the locations where a superconducting line is to be implanted and the stack (E) remains only at the locations where an inductive component is to be implanted.

14. (Currently Amended) Antenna An antenna device comprising an electronic circuit including a superconducting inductive component produced by the method according to one of claims 1 to 10 claim 1.

15. (Currently Amended) ~~Antenna~~ The antenna device according to claim 14, characterized in that wherein the antenna is produced from a superconducting thin film.

16. (Currently Amended) ~~Delay~~ A delay line device comprising an inductive component in ~~series~~ series and a capacitive component in parallel downstream of said inductive component, characterized in that wherein the inductive component is a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.

17. (Currently Amended) ~~Phase~~ A phase shift radar device comprising a plurality of antennas each comprising an electronic circuit including a delay line according to claim 16, ~~this~~ said delay line being arranged such that each of said antennas transmits a signal whose phase is shifted with respect to that of the near antennas.

18. (Currently Amended) ~~Electronic~~ An electronic frequency filtering device comprising an electronic circuit including a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.

19. (Currently Amended) ~~High pass—A high-pass filter device comprising an inductive component in parallel and a capacitive component in series-series downstream of said inductive component, characterized in that wherein~~ the inductive component is a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.

20. (Currently Amended) ~~Low pass—A low-pass filter device comprising a capacitive component in parallel and an inductive component in series-series downstream of said capacitive component, characterized in that wherein~~ the inductive component is a superconducting inductive component produced by the method according to ~~one of claims 1 to 10~~ claim 1.